

Title (en)

A METHOD AND APPARATUS FOR FORMING A THIN LAMINA

Title (de)

VERFAHREN UND VORRICHTUNG ZUR HERSTELLUNG EINER DÜNNSCHICHT

Title (fr)

PROCÉDÉ ET APPAREIL DE FORMATION D'UNE FINE LAMINA

Publication

**EP 2659521 A4 20150513 (EN)**

Application

**EP 11854117 A 20111220**

Priority

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- US 201161510477 P 20110721
- US 201161510476 P 20110721
- US 201161510478 P 20110721
- US 201161510475 P 20110721
- US 2011066195 W 20111220

Abstract (en)

[origin: WO2012092026A2] A method for producing a lamina from a donor body includes implanting the donor body with an ion dosage and heating the donor body to an implant temperature during implanting. The donor body is separably contacted with a susceptor assembly, where the donor body and the susceptor assembly are in direct contact. A lamina is exfoliated from the donor body by applying a thermal profile to the donor body. Implantation and exfoliation conditions may be adjusted in order to maximize the defect-free area of the lamina.

IPC 8 full level

**H01L 31/18** (2006.01); **H01L 21/265** (2006.01); **H01L 21/67** (2006.01); **H01L 21/683** (2006.01); **H01L 21/762** (2006.01); **H01L 31/0224** (2006.01); **H01L 31/042** (2014.01); **H01L 31/056** (2014.01)

CPC (source: EP KR)

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Citation (search report)

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- [I] US 2010159630 A1 20100624 - HILALI MOHAMED M [US], et al
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- See references of WO 2012092026A2

Designated contracting state (EPC)

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KR 20137017692 A 20111220; TW 100149202 A 20111228